

The listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) A device for inspecting element substrates comprising a source of electromagnetic waves and an opposing detector substrate, the source of electromagnetic waves ionizing a gas present between the opposing detector substrate and an element substrate that is to be inspected,

wherein the opposing detector substrate has a TFT and an electrode connected to the TFT.

2. (Original) A device according to claim 1, wherein the source of electromagnetic waves generates electromagnetic waves or X-rays of a wavelength of from 0.01 to 100 nm.

3. (Currently Amended) A device according to claim 1, further comprising [[means]] an ammeter for measuring an electric current between the opposing detector substrate and the element substrate through the ionized gas.

4. (Original) A device according to claim 1, wherein the opposing detector substrate has an opposing detector electrode.

5. (Original) A device according to claim 4, wherein the opposing detector electrode is made of a conductor that permits the transmission of electromagnetic waves or X-rays of a wavelength of 0.01 to 100 nm.

6. (Original) A device according to claim 5, wherein the opposing detector electrode is made of beryllium or aluminum.

7. (Original) A device according to claim 1, wherein the opposing detector substrate has plural TFTs and plural electrodes connected to the TFTs.

8.-9. (Canceled)

10. (Currently Amended) A method of inspecting element substrates by measuring an electric current between the element substrate and an opposing detector substrate through the ionized gas by using a device according to claim 1, thereby to inspect the current-flowing state of the pixel electrodes of the element substrate.

11. (Currently Amended) A method of inspecting element substrates by emitting electromagnetic waves from a source of electromagnetic waves in order to ionize a gas between the opposing detector substrate and the element substrate to be inspected,
wherein the opposing detector substrate has a TFT and an electrode connected to the TFT.

12. (Original) A method according to claim 11, wherein the source of electromagnetic waves generates electromagnetic waves or X-rays of a wavelength of 0.01 to 100 nm.

13. (Currently Amended) A method according to claim 11, wherein a current is measured between the opposing detector substrate and the element substrate through the ionized gas.

14.-15. (Canceled)

16. (New) A device for inspecting element substrates comprising a source of electromagnetic waves and an opposing detector substrate, the source of electromagnetic waves ionizing a gas present between the opposing detector substrate and an element substrate that is to be inspected,

wherein a current control TFT is provided over the element substrate.

17. (New) A device according to claim 16, wherein the source of electromagnetic waves generates electromagnetic waves or X-rays of a wavelength of from 0.01 to 100 nm.

18. (New) A device according to claim 16, further comprising an ammeter for measuring an electric current between the opposing detector substrate and the element substrate through the ionized gas.

19. (New) A device according to claim 16, wherein the opposing detector substrate has an opposing detector electrode.

20. (New) A device according to claim 19, wherein the opposing detector electrode is made of a conductor that permits the transmission of electromagnetic waves or X-rays of a wavelength of 0.01 to 100 nm.

21. (New) A device according to claim 20, wherein the opposing detector electrode is made of beryllium or aluminum.

22. (New) A device according to claim 16, wherein the opposing detector substrate has plural TFTs and plural electrodes connected to the TFTs.

23. (New) A device for inspecting element substrates comprising a source of electromagnetic waves and an opposing detector substrate, the source of electromagnetic waves ionizing a gas present between the opposing detector substrate and an element substrate that is to be inspected,

wherein a current control TFT and a switching TFT are provided over the element substrate.

24. (New) A device according to claim 23, wherein the source of electromagnetic waves generates electromagnetic waves or X-rays of a wavelength of from 0.01 to 100 nm.

25. (New) A device according to claim 23, further comprising an ammeter for measuring an electric current between the opposing detector substrate and the element substrate through the ionized gas.

26. (New) A device according to claim 23, wherein the opposing detector substrate has an opposing detector electrode.

27. (New) A device according to claim 26, wherein the opposing detector electrode is made of a conductor that permits the transmission of electromagnetic waves or X-rays of a wavelength of 0.01 to 100 nm.

28. (New) A device according to claim 27, wherein the opposing detector electrode is made of beryllium or aluminum.

29. (New) A device according to claim 23, wherein the opposing detector substrate has plural TFTs and plural electrodes connected to the TFTs.